

DESCRIPTIVE ABSTRACT

The invention relates to a method for making an anisotropic conductive film with pointed conductive inserts.

5 The method comprises the etching of at least one pattern (C1, K1) in a single crystal substrate (15) in order to form at least one cell (22, 26) with a bottom intended for drawing the contour of an end of an insert (23, 27). The drawing of the pattern is for having at least one protruding tip appear in the bottom of the  
10 cell during the etching of the pattern along the (100) crystallographic plane of the substrate with limiting (111) or (110) planes of the pattern.

The invention is applied to microconnector technology.

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Figs. 4A-4F.